

V2019  
VAKUUM & PLASMA

EFDS 



Die V im  
Zentrum!

8./10. OKTOBER 2019

INTERNAT. CONGRESS CENTER DRESDEN

## Workshop ALD for Industry

Atomic Layer Deposition (ALD) is used to deposit ultraconformal thin films with sub-nm film thickness control. The method is unique in the sense that it employs sequential self-limiting surface reactions for growth in the monolayer thickness regime. During this workshop specially ALD for optical and medical applications will be addressed beside others.

### Organizer:

- *Fraunhofer-Institut für Keramische Technologien und Systeme IKTS, Dresden*
- *Europäische Forschungsgesellschaft Dünne Schichten e.V. (EFDS), Dresden*

### Program Committee:

- *Dr. Jonas Sundqvist, Fraunhofer-Institut für Keramische Technologien und Systeme IKTS, Dresden, Germany*

## Program

### Lecture

Wednesday, October 9, 2019

**Prof. Tuomo Suntola, Finland**

Millenium Technology Prize 2018

### Workshop

Wednesday, 09.10.2019, 16:00 – 17:30

Thursday, 10.10.2019, 09:00 – 12:30 Uhr

#### **„Advances in quantitative characterization of thin films with help of AFM-based methods“**

Malgorzata Kopycinska-Müller, Fraunhofer-Institut für Keramische Technologien und Systeme IKTS, Dresden, Germany

#### **„Conformality in Atomic Layer Deposition“**

Véronique Cremers, Plasma Electronic GmbH, Neuenburg, Germany

#### **„In situ metrology for Atomic Layer Deposition processes“**

Martin Knaut, Technische Universität Dresden, IHM, Dresden, Germany

#### **„Oxides for Electronics“**

Mari Napari, Department of Materials Science and Metallurgy, University of Cambridge, Cambridge, UK

Further presentations will follow soon ...

Changes can occur!